

Notice of References Cited	Application/Control No. 10/632,598	Applicant(s)/Patent Under Reexamination SHEPHERD ET AL.	
	Examiner Michael K. Luhrs	Art Unit 2824	Page 1 of 3

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,280,799	08-2001	Okabe et al.	427/466
	B	US-5,256,339	10-1993	Thornton et al.	264/10
	C	US-6,316,062	11-2001	Sakaguchi et al.	427/570
	D	US-5,244,639	09-1993	Aratani et al.	422/199
	E	US-5,275,967	01-1994	Taniguchi et al.	438/22
	F	US-5,811,030	09-1998	Aoki, Nobuo	516/33
	G	US-6,780,219	08-2004	Singh et al.	75/342
	H	US-6,369,405	04-2002	Canham et al.	257/17
	I	US-5,830,540	11-1998	Bowers, Jim	427/562
	J	US-5,397,429	03-1995	Hummel et al.	216/24
	K	US-2004/0149353	08-2004	Hill, Steven E.	148/033
	L	US-4,226,897	10-1980	Coleman, John H.	438/96
	M	US-5,510,633	04-1996	Orlowski et al.	257/93

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	St. John, J.V. et. al., Formation of Europium Oxide structures on Crystalline Silicon by Spark Processing, Proceedings of the International Symposium on Advanced Luminescent Materials, Chicago, 8-13 Oct. 1985 Electrochem Soc p. 423-31, 1996.
	V	"Above-band-gap photoluminescence from Si fine particles with oxide shell," H. Morisak et al, J. Appl. Phys., 70, pp. 1869-1870, (1991).
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

Notice of References Cited	Application/Control No. 10/632,598	Applicant(s)/Patent Under Reexamination SHEPHERD ET AL.	
	Examiner Michael K. Luhrs	Art Unit 2824	Page 2 of 3

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,552,328	09-1996	Orlowski et al.	438/23
	B	US-5,597,621	01-1997	Hummel et al.	427/554
	C	US-5,723,348	03-1998	Kumomi et al.	438/22
	D	US-6,630,356	10-2003	Armstrong et al.	436/172
	E	US-6,683,367	01-2004	Stalmans et al.	257/618
	F	US-6,780,649	08-2004	Armstrong et al.	436/172
	G	US-2001/0018938	09-2001	Arai et al.	148/301
	H	US-2002/0064606	05-2002	Sakaguchi et al.	427/569
	I	US-6,468,602	10-2002	Sakaguchi et al.	427/570
	J	US-4,772,498	09-1988	Bertin et al.	428/34.4
	K	US-4,861,533	08-1989	Bertin et al.	264/81
	L	US-6,613,276	09-2003	Munir et al.	420/580
	M	US-5,756,924	05-1998	Early, James W.	102/201

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

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	U	
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	W	
	X	

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	Examiner Michael K. Luhrs	Art Unit 2824	Page 3 of 3

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,720,917	02-1998	Matsuura et al.	264/432
	B	US-2003/0151707	08-2003	Kobayashi et al.	349/96
	C	US-6,512,562	01-2003	Kobayashi et al.	349/122
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

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	N					
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